

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method of forming a plurality of films on a base, the method comprising:

setting a plurality of relative positions of at least one nozzle to the base, the setting of the plurality of relative positions including moving at least one of the at least one nozzle and the base;

gasifying a first material by heating the first material to form the first material in a form of gas;

ejecting a first material in ~~a~~the form of gas from the at least one nozzle toward the base at each of the plurality of relative positions; and

detecting an ejection failure of the at least one nozzle.

2. (Previously Presented) The method according to Claim 1, the base being provided in a vacuum atmosphere that is adjusted to a pressure of 10^{-3} torr or less during at least a period in which the ejecting of the first material in the form of gas is carried out.

3. (Previously Presented) The method according to Claim 1, the base being provided in a vacuum atmosphere that is adjusted to a pressure of 10^{-5} torr or less during at least a period in which the ejecting of the first material in the form of gas is carried out.

4. (Previously Presented) The method according to Claim 1, the detecting of the ejection failure of the at least one nozzle including a preliminary ejection of the first material in the form of gas to a preliminary-ejecting area provided in a preliminary member provided in a predetermined area on the base, and

the plurality of films being to be formed in the predetermined area.

5. (Previously Presented) The method according to Claim 1, the detecting of the ejection failure of the at least one nozzle including a preliminary ejection of the first material in the form of gas to a preliminary-ejecting area provided in a preliminary member in a predetermined area on the base, and

the ejection failure being detected on the basis of an inspection of a preliminary film that is formed on the preliminary-ejecting area by the preliminary ejection.

6. (Previously Presented) The method according to Claim 5, the inspection of the preliminary film being performed by a measurement of light-reflectivity of the preliminary film.

7. (Previously Presented) The method according to Claim 5, the inspection of the preliminary film being performed by a measurement of light-transmissivity of the preliminary film.

8. (Previously Presented) The method according to Claim 1, further comprising ejecting a second material in a form of gas from the at least one nozzle,

the detecting of the ejection failure of the at least one nozzle being carried out prior to the ejecting of the second material in the form of gas from the at least one nozzle.

9. (Currently Amended) A method of forming of plurality of films on a base, the method comprising:

setting a first relative position of at least one nozzle to the base, the setting of the first relative position including moving at least one of the at least one nozzle and the base;

forming a first film of the plurality of films on a first area of the base by
ejecting a first material in a form of gas to a first area of the base from the at least one nozzle
at the first relative position, ~~the plurality of films being to be formed in the first area~~position;

setting a second relative position of the at least one nozzle to the base, the setting of the second relative position including moving at least one of the at least one nozzle and the base; and

forming a second film of the plurality of films on a second area of the base by
ejecting the first material in the form of gas ~~to a second area of the base other than the first area~~ from the at least one nozzle at the second relative position,
~~the ejecting of the first material in the form of gas to the second area being carried out prior to the ejecting of the first material in the form of gas to the first area, and each of the plurality of films including the first material.~~

10. (Previously Presented) The method according to Claim 9,
the base being provided in a vacuum atmosphere during at least a period in which the ejecting of the first material in the form of gas to the first area is carried out.

11. (Previously Presented) The method according to Claim 9,
the base being provided in a vacuum atmosphere that is adjusted to 10^{-3} torr or less during at least a period in which the ejecting of the first material in the form of gas to the first area is carried out.

12. (Canceled)

13. (Currently Amended) The method according to Claim 9, further comprising:
forming a third film of the plurality of films on the first film; and
forming a fourth film of the plurality of films on the second film.
~~ejecting a second material in a form of gas to the first area of the base from the at least one nozzle; and~~
~~ejecting the second material in the form of gas to the second area,~~
~~the ejecting of the second material in the form of gas to the second area being carried out prior to the ejecting of the second material in the form of gas to the first area.~~

14. (Currently Amended) The method according to Claim 9, further comprising:
detecting a positional deviation between a first position where a preliminary
film is to be formed by ejecting the first material in the form of gas and a second position
where the preliminary film is actually formed by ejecting the first material in the form of gas.
~~_____ a positional deviation between a first position where a preliminary film is to be~~
~~formed by ejecting of the first material in the form of gas to the second area and a second~~
~~position where the preliminary film is actually formed in the second area by the ejecting the~~
~~first material in the form of gas to the second area being detected, and~~
~~_____ a positional correction of the at least one nozzle being carried out when the~~
~~positional deviation is observed.~~

15. (Currently Amended) A method of manufacturing an electronic device, at least one element of elements constituting the electronic device being formed using the method according to ~~Claim 1~~Claim 9.

16. (Currently Amended) The method according to Claim 15,
~~_____ the first material in the form of gas being~~ used ~~for at least one layer of a~~
~~conductive layer, a semiconductor layer, layer and an insulating layer of the at least one~~
~~element.~~

17. (Previously Presented) The method according to Claim 15, further comprising providing a pattern prior to the ejecting of the first material in the form of gas,
the plurality of films being formed according to the pattern.

18. (Previously Presented) A method of manufacturing an electro-optical device, including a plurality of electro-optical elements, the plurality of electro-optical elements being formed using the method according to Claim 1.

19. (Previously Presented) The method according to Claim 18,

the plurality of electro-optical elements being a plurality of organic electroluminescent elements each of which includes an electron-transporting layer, a hole-transporting layer, a light-emitting layer, and electrodes, and

the first material being used for at least one of the electron-transporting layer, the hole-transporting layer, the light-emitting layer, and the electrodes.

20. (Currently Amended) The method according to Claim 19, further comprising comprising:

_____ forming partitions that separate pixels from each other which are to be formed after the forming of the partitions and each of which corresponds to one of the plurality of electro-optical elements, surround at least one of the light-emitting layer, the electron-transporting layer and the hole-transporting layer.

_____ at least one of the light-emitting layer, the electron-transporting layer, and the hole-transporting layer being surrounded by the partitions.

21-30. (Canceled)

31. (Previously Presented) The method according to Claim 1,
the detecting of the ejection failure of the at least one nozzle being carried out using a sensor.

32. (Currently Amended) The method according to Claim 9, further comprising:

_____ A method of forming a plurality of films on a base, the method comprising:

_____ setting a plurality of relative positions of at least one nozzle to the base, the setting of the plurality of relative positions including moving at least one of the at least one nozzle and the base;

_____ ejecting a first material in a form of gas from the at least one nozzle toward the base at each of the plurality of relative positions; and

sensing at least one film of the plurality of films by a sensor.

33. (Previously Presented) The method according to Claim 32,
the sensing of the at least one film including an irradiation of the at least one film with a light source.
34. (Previously Presented) The method according to Claim 32,
the sensor measuring at least one of a transmission light that transmits the at least one film and a reflection light that is reflected by the at least one film.
35. (Previously Presented) The method according to Claim 32,
the base being provided in a vacuum atmosphere that is adjusted to 10^{-3} torr or less during at least a period in which the ejecting of the first material in the form of gas is carried out.
36. (Currently Amended) A method of forming a plurality of films on a base, the ~~method-ejecting~~ comprising:
ejecting a first material in a form of gas from a nozzle of a plurality of nozzles and a second material in a form of gas from a nozzle of the plurality of nozzles; and
sensing at least one film of the plurality of films by a sensor, the plurality of nozzles moving during at least a part of a period in which the ~~method-ejecting~~ is carried out, and each of the plurality of films including the first material and the second material.
37. (Previously Presented) A method of manufacturing an electronic device, at least one element of elements constituting the electronic device being formed using the method according to Claim 32.
38. (Previously Presented) A method of manufacturing an electronic device, at least one element of elements constituting the electronic device being formed using the method according to Claim 36.

39. (Previously Presented) A method of manufacturing an electro-optical device including a plurality of electro-optical elements, the plurality of electro-optical elements being formed using the method according to Claim 36.

40. (Currently Amended) The method according to Claim ~~39~~18,
the plurality of electro-optical elements being a plurality of organic electroluminescent elements each of which includes an electron-transporting layer, a hole-transporting layer, a light-emitting layer, and electrodes,

the first material and the second material being used for at least one of the electron-transporting layer, the hole-transporting layer, the light-emitting layer, and the electrodes, and

a formation of the light-emitting layer including a co-deposition ~~process~~of a host material and a guest material both of which are included in the light-emitting layer.

41. (Currently Amended) A method of manufacturing an electro-optical device including a plurality of electro-optical elements, the method comprising:

ejecting a first material in a form of gas from a first nozzle of a plurality of nozzles and a second material in a form of gas from a second nozzle of the plurality of nozzles,

the plurality of nozzles ~~moving~~being moved during at least a part of a period in which the ejecting of the first material in the form of gas and the second material in the form of gas is carried out, and

each of the plurality of electro-optical elements including a first layer that ~~plurality of layers one of which~~ includes at least one of the first material and the second ~~material, material.~~

~~the plurality of layers including an electron transporting layer, a hole-transporting layer, a light emitting layer, and electrodes, and~~

~~a formation of the light emitting layer including a co-deposition process.~~

42. (Currently Amended) A method of forming a plurality of films on a base, the method comprising:

ejecting a first material in a form of gas from at least one nozzle toward the base at each of a plurality of relative positions; and

sensing by a sensor at least one film of the plurality of films each of which includes the first material,

a scanning movement of the at least one nozzle being carried out during at least a part of a period in which the ~~method-ejecting~~ is carried out.

43. (Currently Amended) A method of forming a plurality of films on a base, the method comprising:

ejecting a first material in a form of gas from a nozzle of a plurality of nozzles and a second material in a form of gas from a nozzle of the plurality of nozzles; and

sensing at least one film of the plurality of films by a sensor,

a scanning movement of the plurality of nozzles being carried out during at least a part of a period in which the ~~method-ejecting~~ is carried out.

44. (Previously Presented) The method according to Claim 36,
the plurality of nozzles being provided in a discharge head.

45. (Previously Presented) The method according to Claim 44,
the discharge head being constructed to adjust a posture of the discharge head by a θ direction adjusting mechanism, a Z direction adjusting mechanism, and a Y adjusting mechanism.

46. (Previously Presented) The method according to Claim 45,
each of the θ direction adjusting mechanism, the Z direction adjusting mechanism, and the Y adjusting mechanism being operated.

47. (Previously Presented) The method according to Claim 1,
the base being provided in a vacuum atmosphere during at least a period in
which the ejecting the first material is carried out.

48. (Currently Amended) A method of forming a plurality of films on a base, the
method comprising:

detecting an ejection failure of a first nozzle;

setting a first relative position of the first nozzle to the base, the setting of the
first relative position including moving at least one of the first nozzle and the base;

ejecting a first material in a form of gas that is formed by gasifying the first
material by heating the first material from the first nozzle toward the base ~~at the first relative~~
~~position;~~

detecting an ejection failure of a second nozzle;

setting a second relative position of the second nozzle to the base, the setting
of the second relative position including moving at least one of the second nozzle and the
base; and

ejecting a second material in ~~at the~~ form of gas that is formed by gasifying the
second material by heating the second material from the ~~second~~ first nozzle toward the base ~~at~~
~~the second relative position, and each of the plurality of films includes at least one of the first~~
~~material and the second material.~~

49. (New) The method according to Claim 41,
the ejecting of the first material in the form of gas being carried out during at
least a part of a period in which the ejecting of the second material in the form of gas is
carried out.

50. (New) The method according to Claim 41,
the first layer including the first material and the second material.

51. (New) The method according to Claim 50,
the plurality of electro-optical elements being a plurality of organic
electroluminescent elements,
the first material and the second material being included in one of a
light-emitting layer, an electron-transporting layer and a hole-transporting layer that is
included in each of the plurality of organic electroluminescent elements.